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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/716,785	11/19/2003	Wu-Song Huang	FIS920030377US1	6138
32074	7590	08/19/2005	EXAMINER	
INTERNATIONAL BUSINESS MACHINES CORPORATION			LEE, SIN J	
DEPT. 18G			ART UNIT	PAPER NUMBER
BLDG. 300-482			1752	
2070 ROUTE 52				
HOPEWELL JUNCTION, NY 12533				

DATE MAILED: 08/19/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary	Application No.	Applicant(s)	
	10/716,785	HUANG ET AL.	
	Examiner Sin J. Lee	Art Unit 1752	

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

1) Responsive to communication(s) filed on 27 May 2005.

2a) This action is **FINAL**. 2b) This action is non-final.

3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

4) Claim(s) 1-5,7-19 and 21-30 is/are pending in the application.
4a) Of the above claim(s) _____ is/are withdrawn from consideration.

5) Claim(s) _____ is/are allowed.

6) Claim(s) 1-5, 7-19, 21-30 is/are rejected.

7) Claim(s) _____ is/are objected to.

8) Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

9) The specification is objected to by the Examiner.

10) The drawing(s) filed on _____ is/are: a) accepted or b) objected to by the Examiner.

 Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).

 Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).

11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).

a) All b) Some * c) None of:

1. Certified copies of the priority documents have been received.
2. Certified copies of the priority documents have been received in Application No. _____.
3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

* See the attached detailed Office action for a list of the certified copies not received.

Attachment(s)

1) Notice of References Cited (PTO-892)
2) Notice of Draftsperson's Patent Drawing Review (PTO-948)
3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)
Paper No(s)/Mail Date _____.
4) Interview Summary (PTO-413)
Paper No(s)/Mail Date. _____.
5) Notice of Informal Patent Application (PTO-152)
6) Other: _____.

DETAILED ACTION

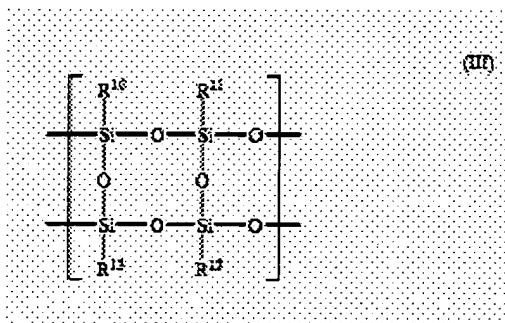
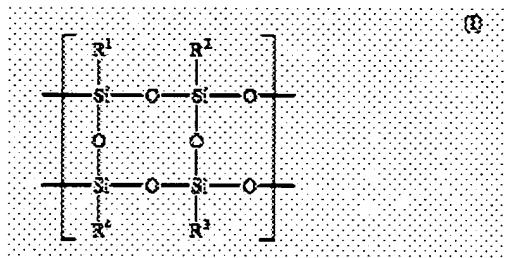
1. Applicants canceled claims 6 and 20.
2. In view of the amendment of May 27, 2005, previous 102(b) rejection on claims 1-4, 10, 11-18, 24-27 and 30 over Sooriyakumaran et al'520 and previous 103(a) rejection on claims 28 and 29 over Sooriyakumaran et al'520 in view of Khojasteh et al'204 is hereby withdrawn.
3. **THIS ACTION IS MADE FINAL.** Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

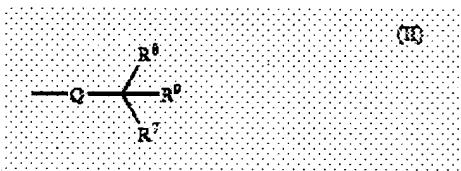
Claim Rejections - 35 USC § 103

4. The text of those sections of Title 35, U.S. Code not included in this action can be found in a prior Office action.
5. Claims 1-5, 7-19, 21-27 and 30 are rejected under 35 U.S.C. 103(a) as being unpatentable over Sooriyakumaran et al (US 2002/0081520 A1) in view of Bucchignano et al (6,037,097).

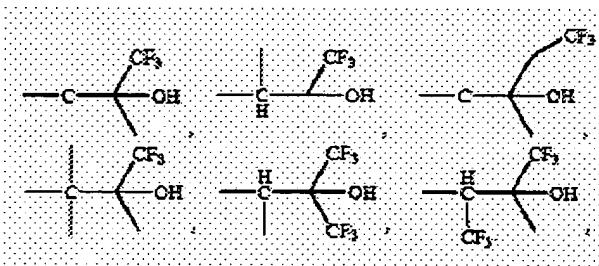
Sooriyakumaran teaches ([0048], [0044], [0045]) a *fluorocarbinol* functionalized *silsesquioxane* copolymer comprised of structure (I) monomer units and monomer units having structure (III):

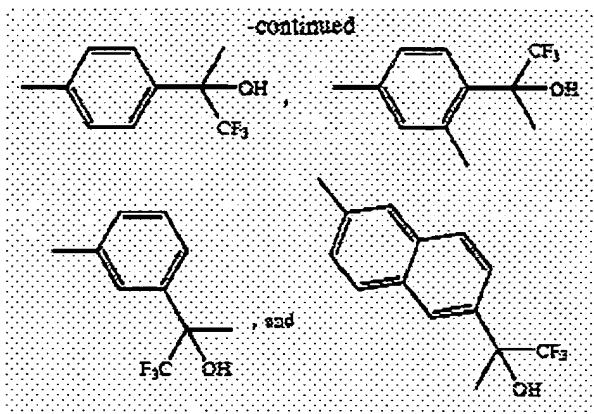


In the structure (I), R¹-R⁴ are independently substituents having following structure (II):



, and Sooriyakumaran teaches ([0047]) following examples for the structure (II):





Sooriyakumaran teaches that in the structure (III), at least one of R^{10-13} is an acid-cleavable moiety (see [0049]). Sooriyakumaran furthermore teaches (see [0050]) that suitable acid-cleavable functionality includes ethers of the formula $-OR^{16}$, in which R^{16} is an acid-cleavable functionality. Sooriyakumaran also teaches a photoacid generator as the second component of his resist composition (see [0056]).

Bucchignano teaches (col.2, lines 21-29, lines 35-53) that by using a cyclic aliphatic ketal substituent as an acid labile protecting group for an aqueous base soluble copolymer, one can obtain a chemically amplified resist that provides improved resist coating shelf life and with little or no vacuum effects on use and that prevents air-borned contaminants from adversely effecting the chemical nature of the aqueous base soluble copolymer. Buchignano teaches a methoxycyclohexanyl group as a highly preferred example for the unsubstituted cyclic aliphatic ketals (see col.4, lines 37-50).

Bucchignano also teaches (col.4, lines 51-58) that hydrogen of the cycloaliphatic portions of the ketal substituent can be substituted with hydrophobic groups such as – CF_3 , $-CHF_2$, $-CH_2F$, $-CCl_3$, $-CHCl_2$, $-CH_2Cl$, and $-Si(CH_3)_3$.

In view of Buccignano's teaching, it would have been obvious to one of ordinary skill in the art to use $-\text{OR}^{16}$ group as Sooriyakumaran's acid-cleavable group in structure (III), in which R^{16} represents either methoxycyclohexanyl group (the $-\text{OR}^{16}$ group, in which R^{16} is methoxycyclohexanyl group, teaches present first formula of claim 1) or methoxycyclohexanyl group substituted with CF_3 , $-\text{CHF}_2$, $-\text{CH}_2\text{F}$, $-\text{CCl}_3$, $-\text{CHCl}_2$, $-\text{CH}_2\text{Cl}$, or $-\text{Si}(\text{CH}_3)_3$, in order to obtain a chemically amplified resist that provides improved resist coating shelf life and with little or no vacuum effects on use and that prevents air-borne contaminants from adversely effecting the chemical nature of the aqueous base soluble copolymer as taught by Buccignano. Therefore, Sooriyakumaran in view of Buccignano would render obvious present inventions of claims 1-5 and 7-10.

With respect to present claim 11, Sooriyakumaran teaches ([0055]) that his copolymer generally has an average Mw in the range of 1,000 to 5,000. Therefore, Sooriyakumaran in view of Buccignano would render obvious present invention of claim 11.

Sooriyakumaran teaches ([0075]) a process for generating a resist image on a substrate which comprises the steps of: (a) coating a substrate with a film comprising his resist composition; (b) imagewise exposing the film to radiation; and (c) developing the image. Sooriyakumaran teaches ([0080]) that the pattern from the resist structure may then be transferred to the material of the underlying substrate by etching. Sooriyakumaran also teaches a post-exposure baking step (see [109]). Therefore,

Sooriyakumaran in view of Bucchignano would render obvious present inventions of claims 14-19, 21-24 and 30.

With respect to present claim 27, Sooriyakumaran teaches that a bilayer substrate may be employed in which his resist composition forms an upper resist layer on top of a bilayer substrate comprised of a base layer and underlayer that lies between the upper resist layer and the base layer. Thus, Sooriyakumaran in view of Bucchignano would render obvious present invention of claim 27.

With respect to present claims 12, 13, 25, and 26, in his Example 3, Sooriyakumaran teaches partial protection of poly(2-hydroxy-3,3,3-trifluoropropylsilsesquioxane) with acid-cleavable trimethylsilyl group. Based on Bucchignano's teaching (i.e., the use of a cyclic aliphatic ketal substituent as an acid labile protecting group for an aqueous base soluble copolymer provides a chemically amplified resist, which has improved resist coating shelf life and with little or no vacuum effects on use and which prevents air-borne contaminants from adversely effecting the chemical nature of the aqueous base soluble copolymer), it would have been obvious to one of ordinary skill in the art to partially protect Sooriyakumaran's poly(2-hydroxy-3,3,3-trifluoropropylsilsesquioxane) with acid-cleavable cyclic aliphatic ketal substituent such as methoxycyclohexanyl group in order to obtain a chemically amplified resist, which has improved resist coating shelf life and with little or no vacuum effects on use and which prevents air-borne contaminants from adversely effecting the chemical nature of the aqueous base soluble copolymer. Such polymer comprises present combination of monomeric units (II) and (III); *in the formula (III)*, X would be a methylene group, R³

would be a H atom, R⁴ would be –CF₃ (a fluorinated alkyl group), q would be 0, and R⁶ would be –OH (a solubility promoting group). In the formula (II), X would be a methylene group, R³ would be a H atom, R⁴ would be –CF₃ (a fluorinated alkyl group), q would be 0, and R⁵ would be methoxycyclohexanyl oxy group (present solubility inhibiting cyclic ketal group). Also, such polymer comprises present combination of monomeric units (II) and (V); in the formula (V), X would be a methylene group, one R³ would be a H atom, another R³ would be –CF₃ (a halogenated alkyl group), q would be 0, and R⁶ would be –OH (a solubility promoting group). Therefore, Sooriyakumaran in view of Buccignano would render obvious present inventions of claims 12, 13, 25, and 26.

6. Claims 28 and 29 are rejected under 35 U.S.C. 103(a) as being unpatentable over Sooriyakumaran et al (US 2002/0081520 A1) in view of Buccignano et al (6,037,097) as applied to claim 27 above, and further in view of Khojasteh et al (US 2002/0058204 A1).

Sooriyakumaran in view of Buccignano is discussed above in Paragraph 5. As discussed above, Sooriyakumaran teaches that a bilayer substrate may be employed in which his resist composition forms an upper resist layer on top of a bilayer substrate comprised of a base layer and underlayer that lies between the upper resist layer and the base layer. Sooriyakumaran does not teach present underlayer composition of claim 28. Khojasteh teaches ([0009]-[0021]) an underlayer composition comprising (a) a polymer containing (i) cyclic ether moieties, (ii) saturated polycyclic moieties, and (iii) aromatic moieties, and (b) an acid generator, or an underlayer composition comprising

(a) a polymer containing (i) saturated polycyclic moieties, and (ii) aromatic moieties, (b) an acid generator, and (c) a crosslinker. Khojasteh teaches that use of such an underlayer composition provide underlayers having outstanding optical, mechanical and etch selectivity properties ([0008]). In view of Khojasteh's teaching, it would have been obvious to one of ordinary skill in the art to use Khojasteh's underlayer composition for Sooriyakumaran's underlayer in order to obtain underlayer having outstanding optical, mechanical and etch selectivity properties as taught by Khojasteh. Khojasteh also teaches ([0058]) that the polymer of the underlayer composition preferably contains a fluorine components such as pentafluoroaryl group and trifluoromethyl group. Therefore, Sooriyakumaran in view of Khojasteh and further in view of Khojasteh would render obvious present inventions of claims 28 and 29.

Response to Arguments

7. Applicants argue that Bucchignano fails to teach or suggest a resist having a silsesquioxane backbone and a solubility inhibiting cyclic ketal pendant acid-labile moiety having a low activation energy for acid-catalyzed cleaving, unlike the present invention which is useful for photolithographic imaging methods. Applicants furthermore argue that there is no motivation to combine the teachings of Sooriyakumaran with the teachings of Bucchignano to arrive at the present invention.

First of all, the Examiner never asserted that Bucchignano teaches a resist having a silsesquioxane backbone and a solubility inhibiting cyclic ketal pendant acid-labile moiety having a low activation energy for acid-catalyzed cleaving. It is the teachings of Sooriyakumaran *in view of* Bucchignano (*not Bucchignano alone*) which

render obvious present resist. It is also the Examiner's position that she has established a proper motivation to combine the teachings of Sooriyakumaran with the teaching of Bucchignano. That is, since Bucchignano (which also teaches a lithographic process) teaches that by using a cyclic aliphatic ketal substituent (such as methoxycyclohexanyl group) as an acid labile protecting group for an aqueous base soluble copolymer (with respect to the aqueous base soluble copolymer, Bucchignano states in col.2, lines 56-59 that the aqueous base soluble polymer or copolymer contains a polymer backbone including but not limited to: polyolefins, polyolefin sulfones, polyketones, polyethers and the like), one can obtain a chemically amplified resist that provides *improved resist coating shelf life* and with little or no vacuum effects on use and that prevents air-borne contaminants from adversely effecting the chemical nature of the aqueous base soluble copolymer, it would have been obvious to one of ordinary skill in the art to use -OR¹⁶ group as Sooriyakumaran's acid-cleavable group in structure (III), in which R¹⁶ represents a methoxycyclohexanyl group in order to obtain a chemically amplified resist that provides *improved resist coating shelf life* and with little or no vacuum effects on use and that prevents air-borne contaminants from adversely effecting the chemical nature of the aqueous base soluble copolymer as taught by Bucchignano. Therefore, it is still the Examiner's position that Sooriyakumaran in view of Bucchignano render obvious present inventions.

8. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Sin J. Lee whose telephone number is 571-272-1333.

The examiner can normally be reached on Monday-Friday from 9:00 am EST to 5:30 pm EST.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Cynthia Kelly, can be reached on 571-272-1526. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

S. J. L.
S. Lee
August 16, 2005

S. J. Lee
SIN LEE
PRIMARY EXAMINER